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(71) Applicant and

(72) Inventor: IKENOUCHI, Sumifusa [JP/JP]; 491-2,
Yanagihara, Hojo-shi, Ehime 7992434 (JP).

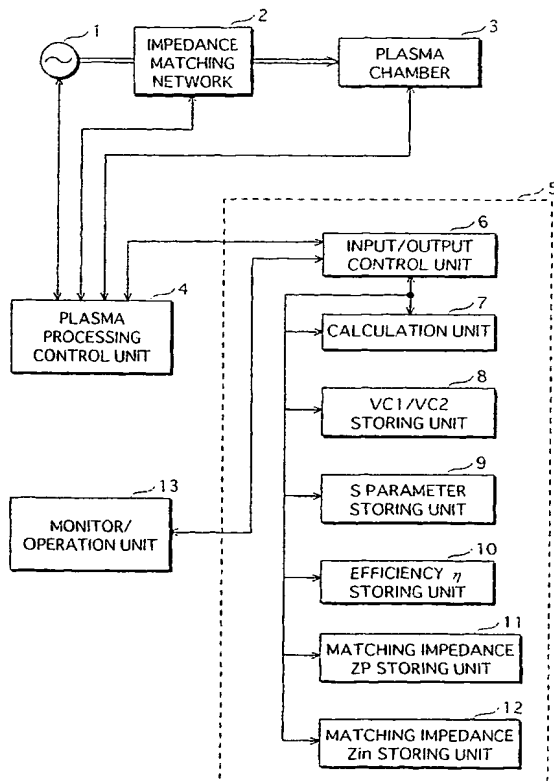
(74) Agent: NAKAJIMA, Shiro; 6F, Yodogawa 5-Bankan,
2-1, Toyosaki 3-chome, Kita-ku, Osaka-shi, Osaka
5310072 (JP).

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(54) Title: PLASMA PROCESSING APPARATUS, CONTROL METHOD FOR PLASMA PROCESSING APPARATUS, AND
EVALUATION METHOD FOR PLASMA PROCESSING APPARATUS



(57) Abstract: A plasma processing apparatus comprises:
an RF generator operable to output RF power; an impedance
matching network operable to receive the RF power; a
plasma chamber operable to receive an output from the
impedance matching network; a storing unit operable to store
information relating to an S parameter of the impedance
matching network; and a control unit operable to control
an operating condition for the plasma chamber, based on the
information relating to the S parameter.



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